

AMENDMENTS TO THE CLAIMS

Claims 1-6 (canceled).

Claims 7-10 (withdrawn).

Claim 11 (new). A precious metal magnetic sputtering target comprising a mechanically alloyed, chemically homogeneous alloy composition having microstructural homogeneity, said alloy composition comprising Pt, Co, and at least 2 atomic % of at least one element selected from the group consisting of Cr, B, Ta, Nb, C, Mo, W, Zr, Zn, Cu, Hf, O, Si and N.

Claim 12 (new). The sputtering target according to claim 11, wherein said alloy comprises Pt, Co and at least 2 atomic % Cr, Ta and B.

Claim 13 (new). The sputtering target according to claim 11, wherein said alloy comprises Pt, Co and at least 2 atomic % Cr and B.

Claim 14 (new). The sputtering target according to claim 11, wherein said alloy contains multiple phases comprising CoB, CoCrB, CoCr, CoPt, CoCrPt, and Pt uniformly distributed in the alloy.

Claim 15 (new). The sputtering target according to claim 11, wherein said alloy comprises a CoCrPtTaB alloy.

Claim 16 (new). The sputtering target according to claim 15, wherein said alloy comprises Co-20Cr-10Pt-2Ta-5B.

Claim 17 (new). The sputtering target according to claim 11, wherein said alloy is an CoCrPtB alloy.

Claim 18 (new). The sputtering target according to claim 17, wherein said alloy comprises Co-19Cr-11Pt-8B.

Claim 19 (new). The sputtering target according to claim 17, wherein said alloy comprises Co-15Cr-11Pt-10B.

Claim 20 (new). The sputtering target according to claim 7, wherein said alloy comprises Co-20Cr-10Pt-6B.

Claim 21 (new). The sputtering target according to claim 7, wherein said alloy comprises Co-10Cr-10Pt-20B.

Claim 22 (new). The sputtering target according to claim 7, wherein said alloy comprises Co-12Cr-12Pt-18B.

Claim 23 (new). The sputtering target according to claim 7, wherein said alloy comprises Co-12Cr-8Pt-22B.

Claim 24 (new). The sputtering target according to claim 11, wherein the atomic % of the element ranges from 2% to 30%.

Claim 25 (new). The sputtering target according to claim 11, wherein the alloy composition has point to point compositional uniformity having a standard deviation ranging from 0.004 to 0.067.

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Claim 26 (new). The sputtering target according to claim 11, wherein the alloy composition has been rapidly solidified.